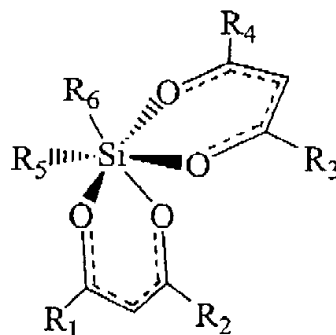


**Amendments to the Claims:**

1. (currently amended) A **solvent CVD precursor** solution including **a solvent component and** a hexacoordinated silicon beta-diketonate composition of the formula  $R_2Si(\beta\text{-diketonate})_2$  or  $(RO)_2Si(\beta\text{-diketonate})_2$ , wherein each R is the same as or different from the other R, and each R is independently selected from H, aryl, fluoroaryl,  $C_1 - C_{12}$  alkyl,  $C_1 - C_{12}$  fluoroalkyl, and  $C_1 - C_{12}$  silicon-containing alkyl.
2. (currently amended) The **solvent precursor** solution of claim 1, wherein each  $\beta$ -diketonate ligand of the composition may be the same as or different from the other  $\beta$ -diketonate ligand of the composition, and is independently selected from: 2,2,6,6-tetramethyl-3,5-heptanedionate; 1,1,1,2,2,3,3-hepta-fluoro-7,7-dimethyloctane-4,6-dionate; acetylacetonate; trifluoro-acetylacetonate; and hexafluoroacetylacetonate.
3. (currently amended) The **solvent precursor** solution of claim 1, wherein each  $\beta$ -diketonate ligand of the composition is 2,2,6,6-tetramethyl-3,5-heptanedionate.
4. (currently amended) The **solvent precursor** solution of claim 1, wherein the composition is of the formula  $R_2Si(\beta\text{-diketonate})_2$ .
5. (currently amended) The **solvent precursor** solution of claim 1, wherein the composition is of the formula  $(RO)_2Si(\beta\text{-diketonate})_2$ .
6. (currently amended) The **solvent precursor** solution of claim 1, wherein the composition is of the formula  $(t\text{-BuO})_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2$ .
7. (currently amended) The **solvent precursor** solution of claim 1, wherein the composition is of the formula  $(CH_3)_2Si(2,2,6,6\text{-tetramethyl-3,5-heptanedionate})_2$ .
8. (previously canceled)

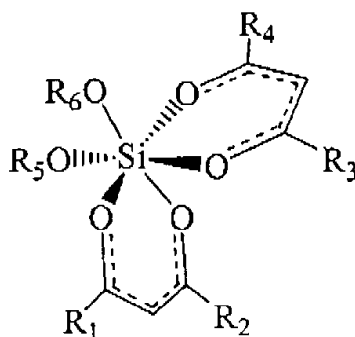
9. (currently amended) The **solvent precursor** solution of claim 1, **wherein said solvent component comprises** including a hydrocarbon solvent.
10. (currently amended) The **solvent precursor** solution of claim 1, **wherein said solvent component comprises** including octane.
11. (currently amended) A **precursor solution for use in chemical vapor deposition, comprising a solvent component and a** silicon  $\beta$ -diketonate **for use in chemical vapor deposition and** of the formula:



wherein:

- $R_1$ ,  $R_2$ ,  $R_3$  and  $R_4$  are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl,  $C_1 - C_{12}$  alkyl,  $C_1 - C_{12}$  fluoroalkyl, and  $C_1 - C_{12}$  silicon-containing alkyl; and
- $R_5$  and  $R_6$  are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl,  $C_1 - C_{12}$  alkyl,  $C_1 - C_{12}$  fluoroalkyl, and  $C_1 - C_{12}$  silicon-containing alkyl.

12. (currently amended) A precursor solution for use in chemical vapor deposition, comprising a solvent component and a silicon  $\beta$ -diketonate for use in chemical vapor deposition and of the formula:



wherein:

$R_1$ ,  $R_2$ ,  $R_3$  and  $R_4$  are the same as or different from one another, and wherein each of such substituents is independently selected from H, aryl, fluoroaryl,  $C_1 - C_{12}$  alkyl,  $C_1 - C_{12}$  fluoroalkyl and  $C_1 - C_{12}$  silicon-containing alkyl; and  $R_5$  and  $R_6$  are same as or different from one another, and each is independently selected from H, aryl, fluoroaryl,  $C_1 - C_{12}$  alkyl,  $C_1 - C_{12}$  fluoroalkyl, and  $C_1 - C_{12}$  silicon-containing alkyl.

13-34. (previously canceled)

35. (new) A novel composition comprising  $(t\text{-OBu})_2\text{Si}(\text{thd})_2$ .

36. (new) A novel composition comprising  $(\text{CH}_3)_2\text{Si}(\text{thd})_2$ .